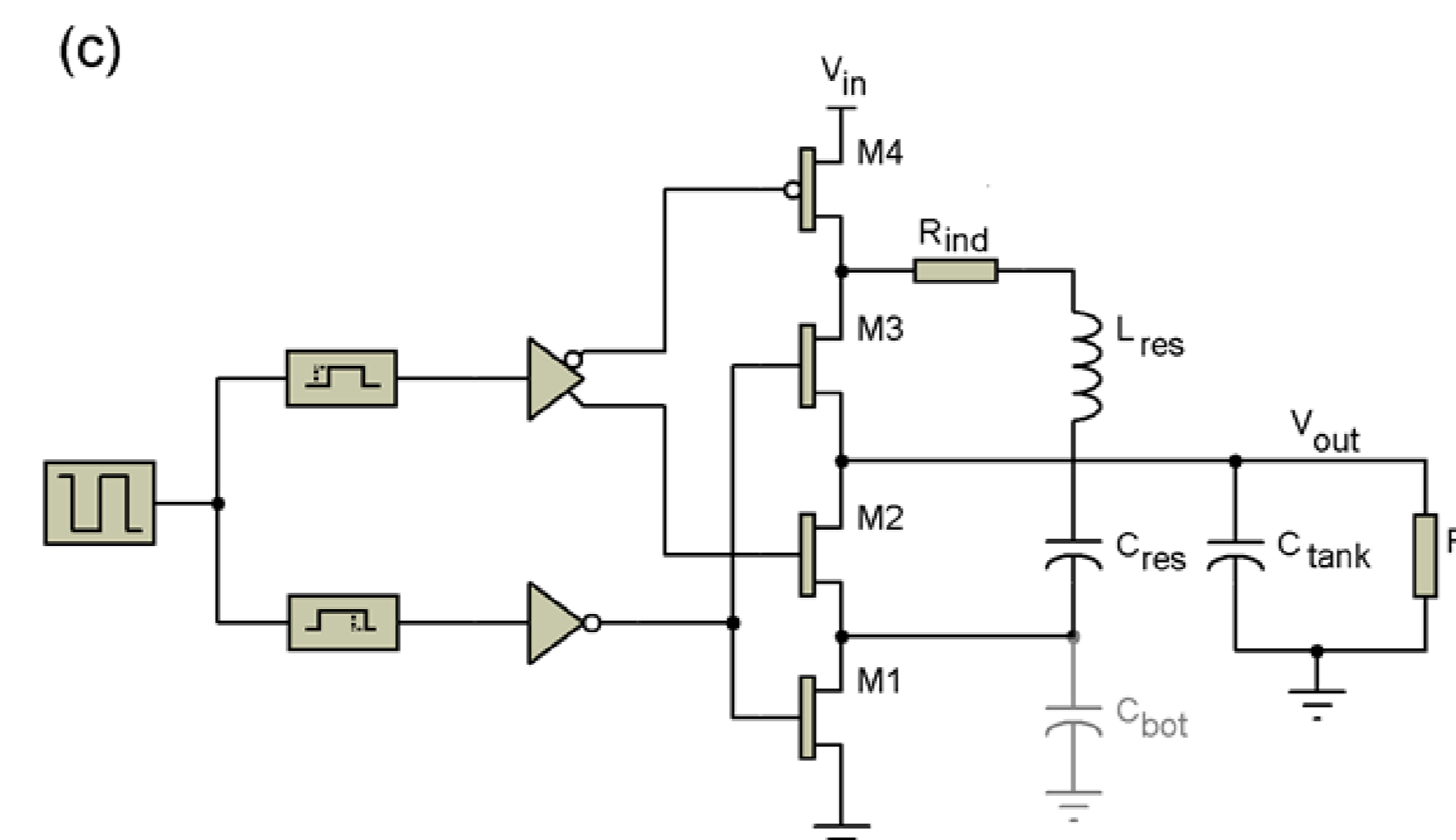
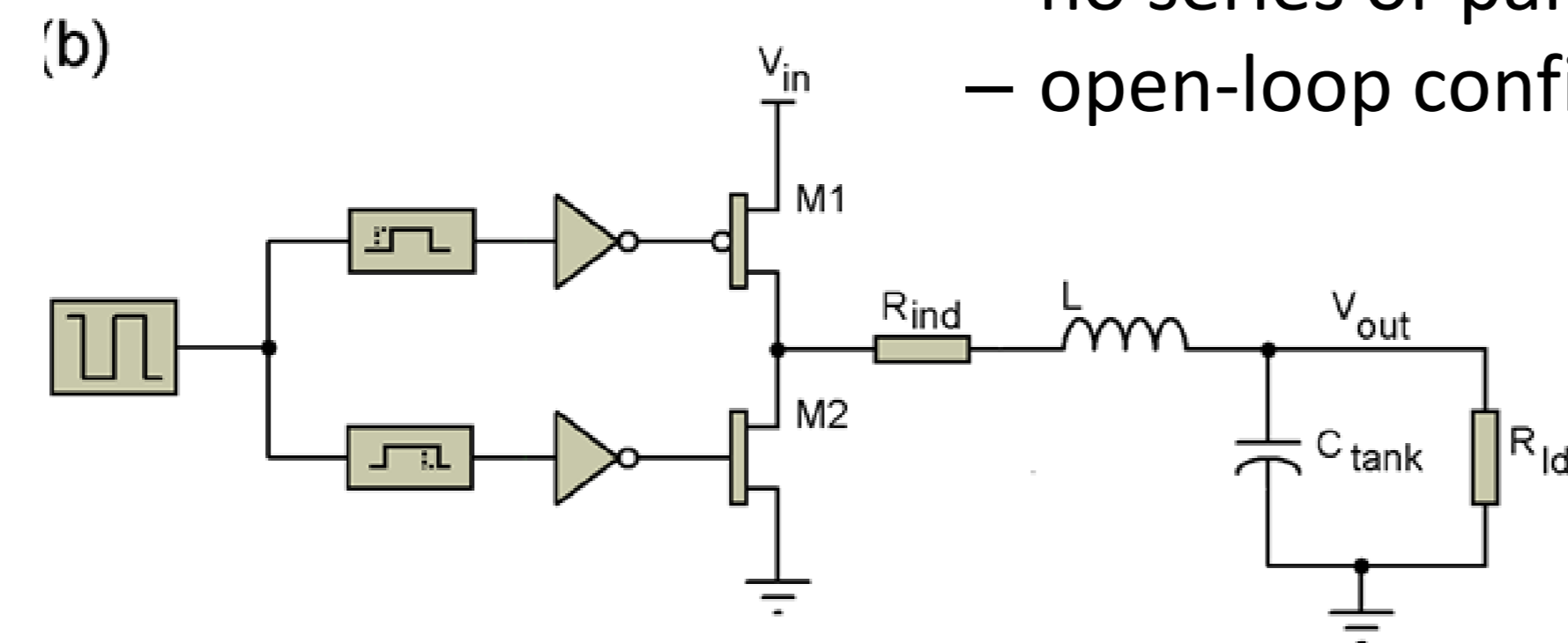
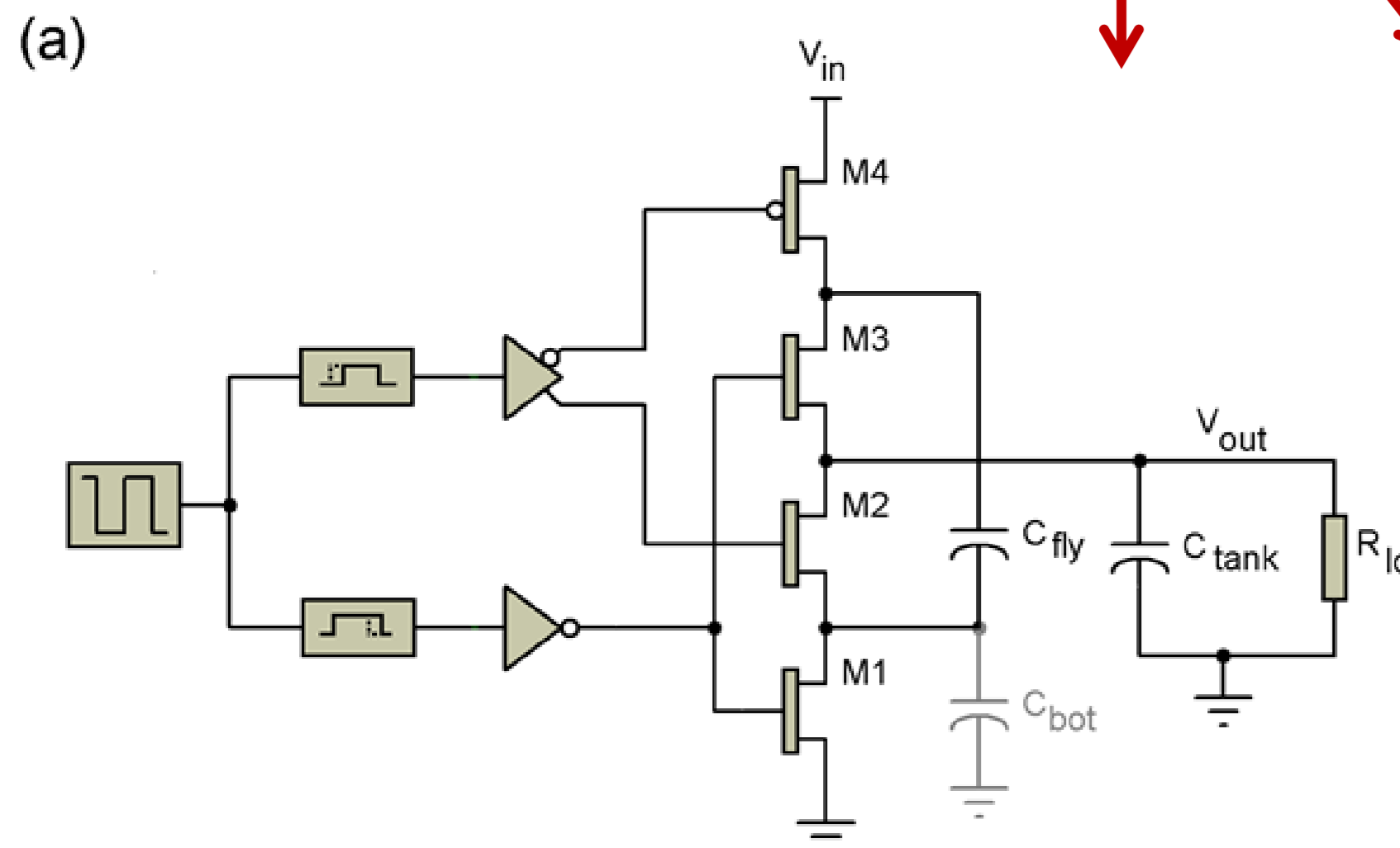
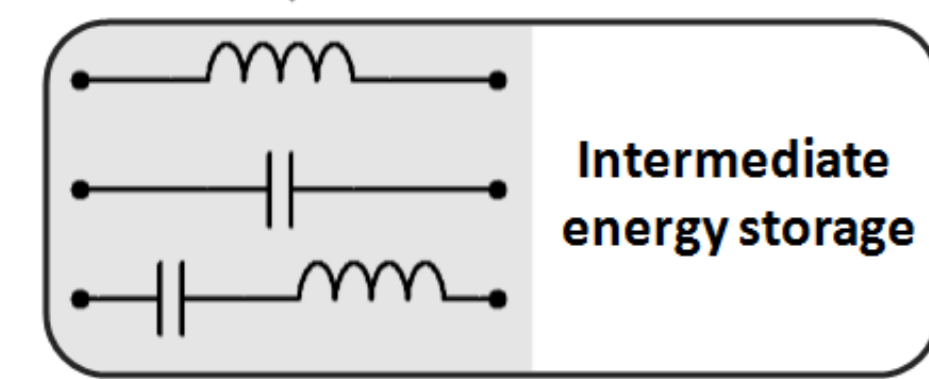
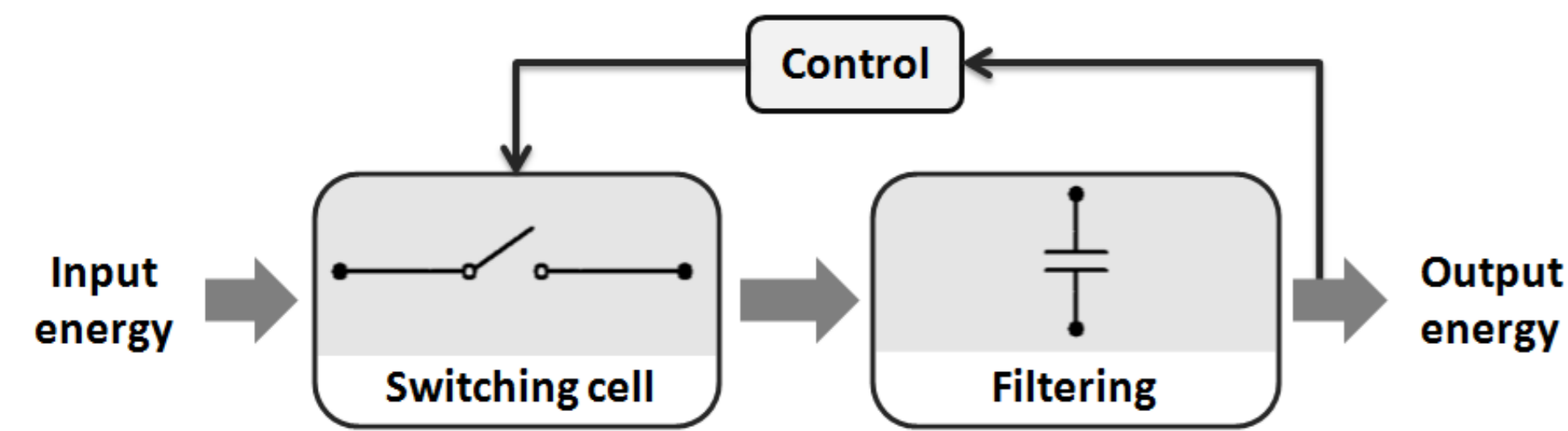


Objective

What is the “best” topology for the full integration of DC-DC converters in CMOS technology to achieve the highest efficiency on a fixed silicon die area?



(a) capacitive (b) inductive and (c) resonant-based converter under study

Methods

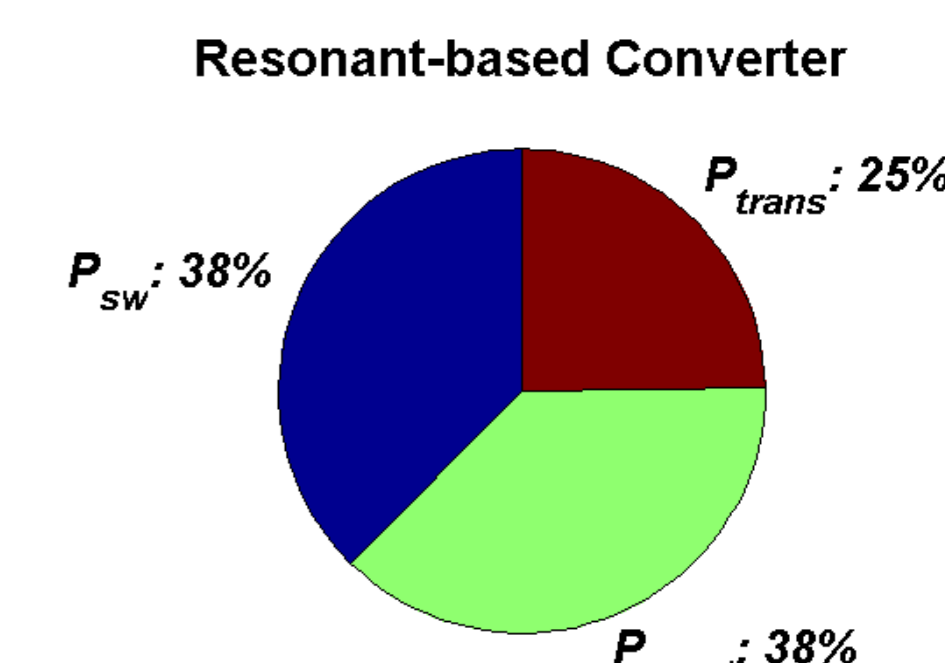
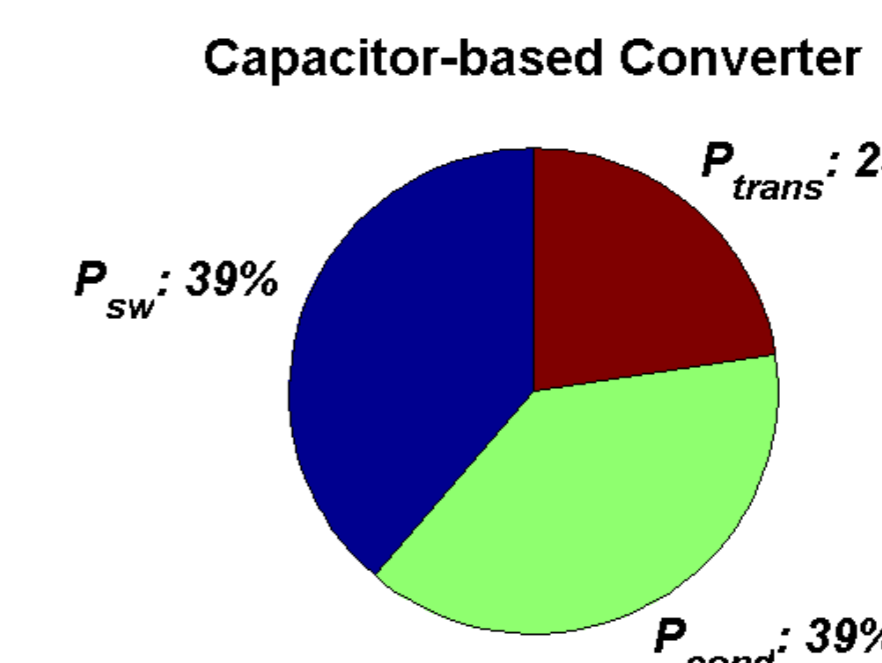
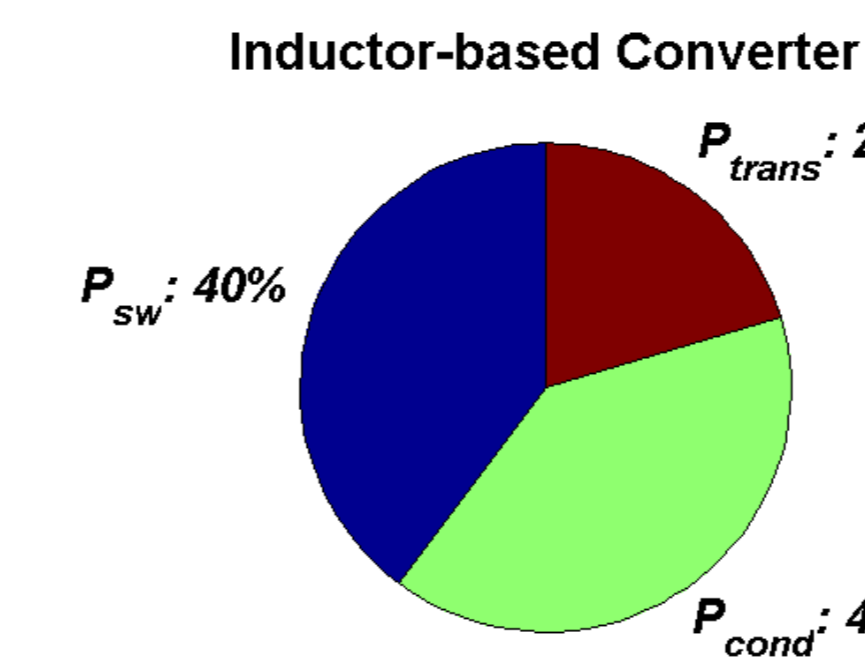
- Perform 3x3 comparisons
 - for three topologies (a,b,c)
 - for three load resistor value (0.08,0.8,8Ω)
- Use standard CMOS 65nm (ST)
 - no external component
 - cap: nw/poly and metal/metal (M1-5)
 - ind: air-core (M3-7, 1 spire)
 - resonant surface: 1/3 ind, 2/3 cap
 - thick oxide MOSFET
- Design basic topology (no refinements)
 - no interleave, no coupled ind
 - no series or parallel connection
 - open-loop configuration

Modeling & Optimization

- Identify loss mechanism
 - Switching loss P_{sw}
 - Conduction loss P_{cond}
 - Energy transfer related loss P_{trans}
- Optimize the sizing $\{W, \theta_i, f_{sw}, L, C\}$
 - Efficiency driven optimization
 - First based on analytical equations
 - Then based on transistor-level simulation

Converter	Inductive	Capacitive	Resonant
P_{sw}	$A f_{sw} W$	$A f_{sw} W$	$A f_{sw} W$
P_{cond}	$\frac{F}{W} (\theta_1 + G \theta_2) \left(1 + \frac{H}{L^2 f_{sw}^2}\right)$	$\frac{B}{W} \sum \theta_i$	$\frac{\pi^2}{8} \frac{B}{W} \sum \theta_i$
P_{trans}	$JL \left(1 + \frac{H}{L^2 f_{sw}^2}\right)$	$C \left(1 + D f_{sw} + \frac{E}{f_{sw}}\right)$	$\frac{K}{\alpha} \left(1 + \frac{N}{f_{res}^2 \sqrt{1-\alpha}}\right) + Q \alpha f_{res}$

Losses analytical expressions

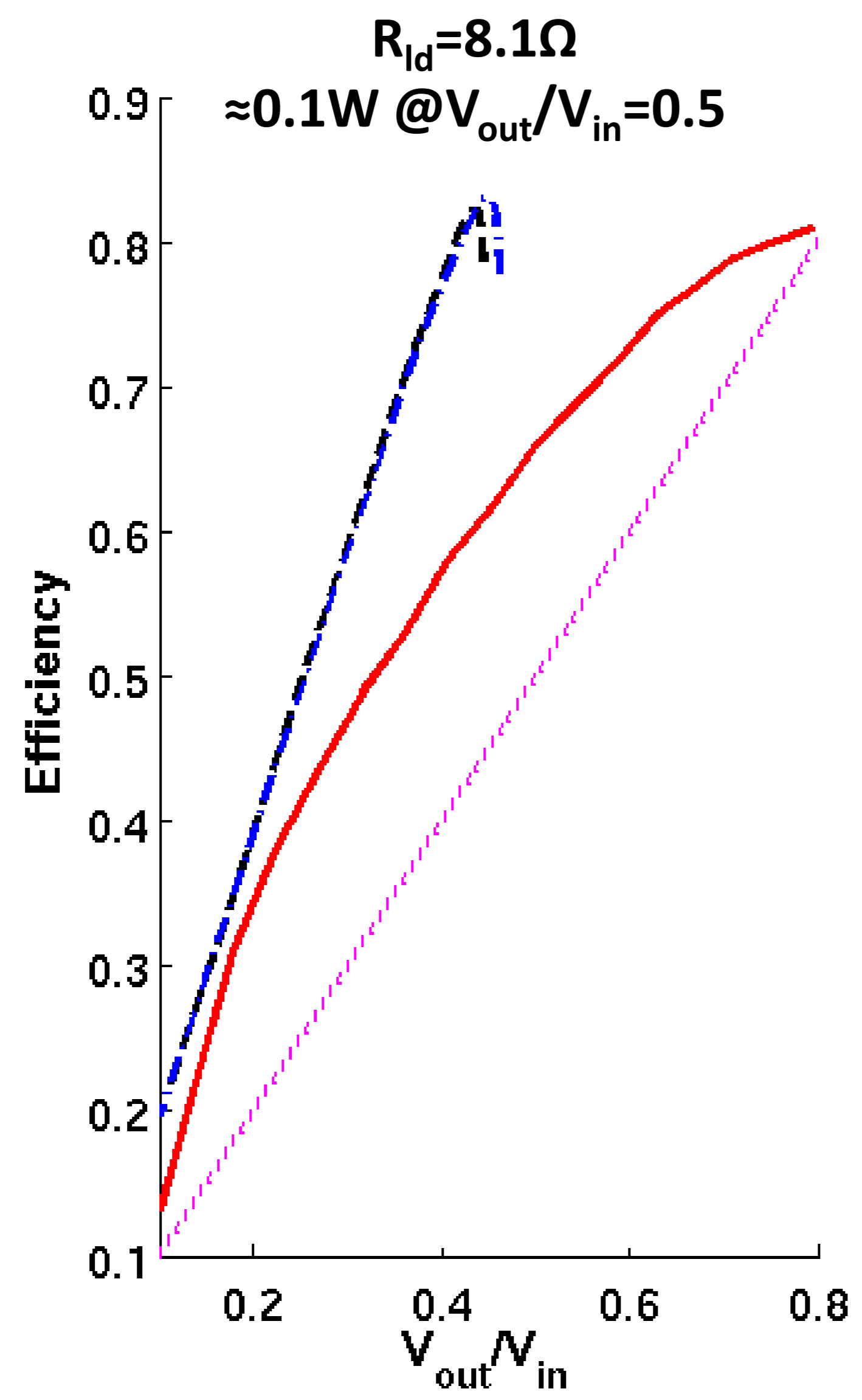


Losses distribution @Rld=0.81Ω

Results

Conclusion

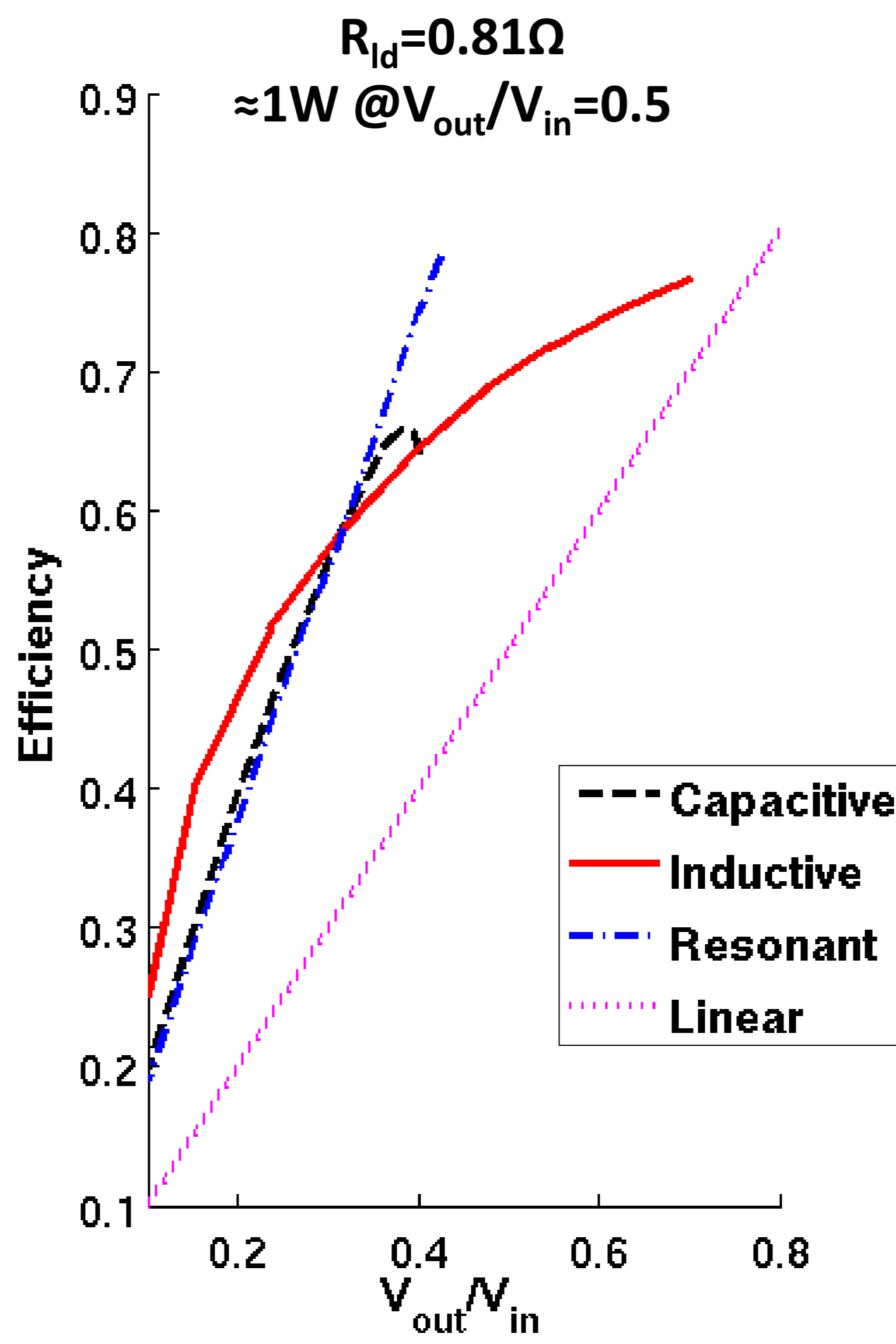
Process /design parameters	Value
Input voltage	1.8V
Passive area	1mm ²
Optimized point	0.9V
Switch voltage rating	2.5V
Bypass capacitor (C _{tank})	300nF
Switch resistivity	1.3kΩ.μm
Switch capacitance	1fF/μm
Capacitance density	16fF/μm ²
Bottom plate capacitance	2%
Indutance FoM	7nH/Ω



inductive < capacitive ≈ resonant

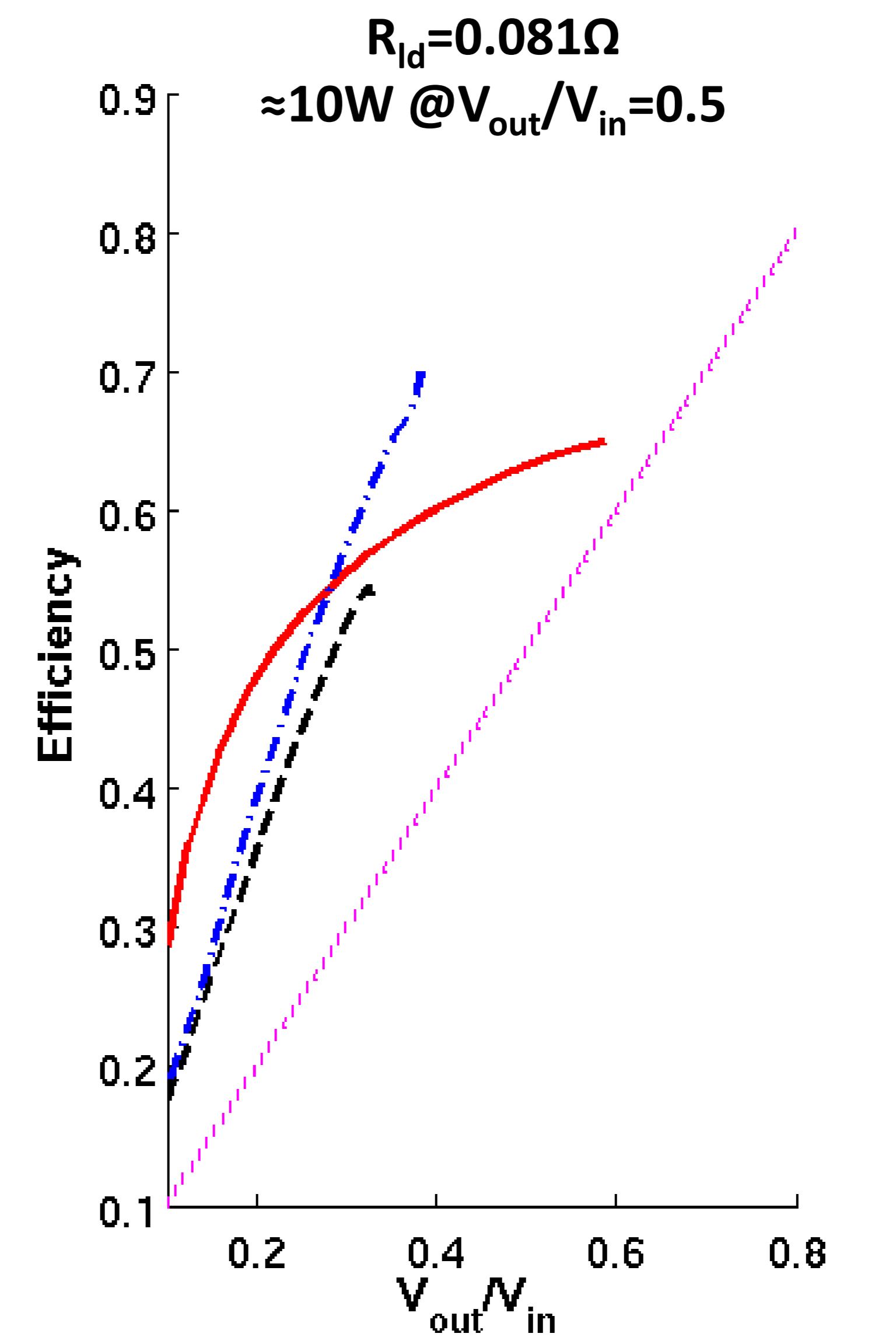
Optimal Sizing →
Passive value (on 1mm ²)
Switching frequency [MHz]
Active area overhead [%]
Passive energy density [nJ/mm ²]

Inductive	Capacitive	Resonant
4.2nH	16nF	0.5nH / 11nF
160	15	67
2	2	3
0.07	6.5	4.5



inductive ≈ capacitive < resonant

Inductive	Capacitive	Resonant
0.9nH	16nF	0.3nH / 11nF
170	50	88
6	11	6
0.3	6.5	4.7



capacitive < inductive < resonant

Inductive	Capacitive	Resonant
0.2nH	16nF	0.06nH / 11nF
145	400	200
60	56	140
0.9	6.5	6.0

- Passive energy density is not directly linked to efficiency
- Capacitive switching converter seems to be a relevant solution up to 0.1W/mm²
- At higher power density, resonant achieves better performance
- Results strongly depend on the technology capability to integrate passive!

Discussion is open...

References

Many thanks to previous works in this topic

- [1] S. R. Sanders et al. "The Road to Fully Integrated DC-DC Conversion via the Switched-Capacitor Approach," 2013
- [2] C.R. Sullivan et al., "Integrating Magnetics for On-Chip Power: A Perspective," 2013
- [3] T. Andersen et al., "A 4.6W/mm² Power Density 86% Efficiency On-Chip Switched Capacitor DC-DC Converter in 32nm SOI CMOS," 2013
- [4] Y.K. Ramadass et al., "A Fully-Integrated Switched-Capacitor Step-Down DC-DC Converter with Digital Capacitance Modulation in 45 nm CMOS," 2010
- [5] J. Wibben, R. Harjani, "A High-Efficiency DC-DC Converters Using 2nH Integrated Inductors," 2008
- [6] F. Neveu et al., "Review of High Frequency, Highly Integrated Inductive DC-DC Converters," 2014
- [7] K. Kesarwani et al. "A 2-Phase Resonant Switched-Capacitor Converter Delivering 4.3W at 0.6W/mm²," 2014
- [8] M.D. Seeman, "A Comparative Analysis of Switched-Capacitor and Inductor-Based DC-DC Conversion Technologies," 2010
- [9] R. Aparicio, A. Hajimiri, "Capacity Limits and Matching Properties of Integrated Capacitors," 2002
- [10] S. Osmanaj, E. Nasufi, "Design of an Integrated Planar Inductor Using 0.35μm Fabrication Technology," 2013

..and others

Efficiency vs conversion ratio over three nominal loads - results from transistor-level simulation